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PATENT APPLICATION 04-18-02



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of

Cathie J. BURKE et al.

Application No.: 10/046,245

Group Art Unit: 1756

Filed: January 16, 2002

Docket No.: 106452

For: METHODS OF PATTERNING RESISTS AND STRUCTURES INCLUDING THE  
PATTERNED RESISTS

INFORMATION DISCLOSURE STATEMENT

Director of the U.S. Patent and Trademark Office  
Washington, D.C. 20231

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.

Respectfully submitted,



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JAO:JAD/ldg

Date: April 10, 2002

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Form PTO-14 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 106452		APPLICATION NO. 10/046,245	
INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)				APPLICANT(S) Cathie J. BURKE et al.			
				FILING DATE January 16, 2002		GROUP 1756	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	
		5,344,748	9/1994	Feely			
		5,738,799	4/1998	Hawkins et al.			
		5,485,181	1/1996	Convers			
		5,699,094	12/1997	Burke et al.			
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)							
		S. Hagan et al., "Photosensitive Polyimide: Lithography in the Thick-Film Regime," Proceedings 11 <sup>th</sup> International Conference Photopolymers Principles, Processes, and Materials, Society of Plastics Engineers, Inc., Oct. 6-8, 1997, p. 422-437					
EXAMINER				DATE CONSIDERED			
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

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